

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Chiang, Tony P.; Leeser, Karl F.
Assignee: Novellus Systems, Inc. (reassigned)
Title: Method for Integrated In-Situ Cleaning and Subsequent Atomic Layer Deposition Within a Single Processing Chamber
Serial No.: 09/994,279 Filing Date: November 26, 2001
Examiner: David Nhu Group Art Unit: 2818
Docket No.: PA1688 US

San Jose, California
May 18, 2005

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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RESPONSE TO OFFICE ACTION

Dear Sir:

This responds to the Office Action dated February 4, 2005, in the above-identified application. A terminal disclaimer is enclosed. Please amend the application to place all claims in condition for allowance as follows.

Amendments to the claims begin on page 2.

Remarks begin on page 7.

05/26/2005 091 REY 00000001 50226 09354279
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